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Applicant(s): Chih-Ming Ke

Application No.: 10/047,266 (CONF 4511)

Filed: 1/14/2002

Title: Reducing photoresist shrinkage via plasma treatment

Attorney Docket No.: 67,200-641

Group Art Unit:  
1765Examiner:  
Kin Chan ChenCommissioner for Patents  
Alexandria, VA 22313-1450

Do not enter.

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Date: Feb. 11, 2004

Kathy Dixon

K-cc  
3/1/04REQUEST FOR RECONSIDERATION

Dear Sir:

In response to a final Office Action dated Dec. 11, 2003, please enter the following amendment and consider the following remarks.